

TITLE OF THE INVENTION

Inorganic Electroluminescent Device and Method of Fabricating
the Same

5 BACKGROUND OF THE INVENTION

Field of the Invention

The present invention relates to an inorganic electroluminescent device and a method of fabricating the same.

10 DISCRIPTION OF THE BACKGROUND ART

Conventionally, inorganic electroluminescent devices (hereinafter abbreviated to inorganic EL devices) have drawn attention as flat light emitting type devices. In an inorganic EL device, a high electric field is applied to a light emitting layer made of an inorganic material so as to cause electrons to accelerate in this electric field and collide with a luminescent center, so that the luminescent center is excited to emit light.

In particular, inorganic EL devices having a light emitting layer principally composed of an alkaline earth sulfide and doped with Eu(europium) provide red light emission with high color purity. Therefore they have conventionally been regarded as components of great prospects.

JP 64-27194 A, for example, describes an inorganic EL device employing a mixed crystal of CaS(calcium sulfide) and

MgS(magnesium sulfide) as a material of a light emitting layer. In the inorganic EL device, a transparent electrode, a first insulator layer composed of Ta₂O₅, a light emitting layer composed of Mg_{0.4}Ca_{0.6}S:Eu, a second insulator layer composed of 5 Al₂O₃, and an upper electrode are formed on a glass substrate in this order.

The aforementioned publication describes that the inorganic EL device disclosed therein can provide improved luminance and efficiency while maintaining high color purity, 10 through the use of the mixed crystal of CaS and MgS as a material of the light emitting layer.

In the conventional inorganic EL device, however, further improving crystallinity and optical characteristics of the light emitting layer requires MgCaS to be formed at 15 increased temperatures. However, increasing the temperature actually degrades crystallinity and therefore deteriorates optical characteristics. For this reason, an inorganic EL device having sufficiently good luminous characteristics has not been realized.

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SUMMARY OF THE INVENTION

An object of the present invention is to provide an inorganic electroluminescent device having good luminous characteristics and a method of fabricating the same.

25 An inorganic electroluminescent device according to one

aspect of the present invention comprises in the following order; an underlayer formed of a first compound semiconductor of Group IIa-VIb; and a light emitting layer formed of a second compound semiconductor of Group IIa-VIb, wherein the first 5 compound semiconductor and the second compound semiconductor have the same crystalline structure.

In the inorganic electroluminescent device according to this invention, on the underlayer formed of the first compound semiconductor of Group IIa-VIb, the light emitting layer formed 10 of the second compound semiconductor of Group IIa-VIb having the same crystalline structure as that of the first compound semiconductor is provided. This allows the crystallinity of the light emitting layer to be improved when the light emitting layer is formed at an increased temperature so that the good 15 optical characteristics can be obtained. As a result, an inorganic electroluminescent device having good luminous characteristics can be realized.

The second compound semiconductor is preferably doped with a substance acting as a luminescent center. The 20 underlayer and the light emitting layer may be provided between a first electrode and a second electrode. Moreover, the inorganic EL device preferably comprises the underlayer and the light emitting layer on a substrate in this order.

The underlayer may be doped with a substance acting as 25 a luminescent center. In this case, the underlayer as well

as the light emitting layer is allowed to emit light.

Preferably, the first compound semiconductor and the second compound semiconductor have a rock-salt structure. In this case, on the underlayer having a rock-salt structure, the 5 light emitting layer having the same rock-salt structure is provided, whereby the crystallinity of the light emitting layer is further improved when the light emitting layer is formed at an increased temperature.

The first compound semiconductor and the second compound 10 semiconductor may have an orientation in an <100> direction. This allows the crystallinity of the light emitting layer to be improved to achieve good optical characteristics.

The bandgap of the first compound semiconductor may be larger than the bandgap of the second compound semiconductor. 15 In this case, the light emitted from the light emitting layer formed of the second compound semiconductor is taken out transmitting through the underlayer composed of the first compound semiconductor without being absorbed by the underlayer. Consequently, a sufficiently high luminance is 20 achieved.

The inorganic EL device may comprise the first electrode, the underlayer, the light emitting layer and the second electrode on the substrate in this order, wherein the substrate and the first electrode are preferably formed of optically 25 transparent materials that can transmit the light emitted from

the light emitting layer.

In this case, the light emitted from the light emitting layer is sufficiently taken out transmitting through the first electrode and the substrate. Consequently, a sufficiently 5 high luminance is achieved.

The first compound semiconductor may contain magnesium and sulfur, and the second compound semiconductor may contain magnesium and sulfur.

In this case, the light emitting layer containing 10 magnesium and sulfur is formed on the underlayer containing magnesium and sulfur, whereby the underlayer acts to prevent lack of sulfur in the light emitting layer during formation of the light emitting layer at an increased temperature. This allows the crystallinity of the light emitting layer to be 15 improved to achieve good optical characteristics.

The second compound semiconductor may further comprise calcium. In this case, the second compound semiconductor contains calcium in addition to magnesium and sulfur, thereby achieving red color light emission with high color purity.

20 The second compound semiconductor may contain $Mg_{1-x}Ca_xS$, wherein the Ca composition ratio x may be $0.1 \leq x \leq 0.15$. This enables red color light emission with high color purity corresponding to the red color of a CRT(cathrode-ray tube).

25 Preferably, the thickness of the underlayer is not larger than 500 nm. Consequenly, it becomes possible to lower

emission initiation volatage while maintaing high luminous intensity. Accordingly, power consumption can be reduced.

More preferably, the thickness of the underlayer is not larger than 200 nm. In this case, it becomes possible to 5 further lower the emission initiation voltage while maintaining high luminous intensity. Accordingly, power consumption can be further reduced.

The thickness of the light emitting layer is preferably larger than the thickness of the underlayer. This provides 10 a high luminous intensity. Also, light absorption at the underlayer is suppressed.

The light emitting layer may contain a rare earth element or a transition metal element as a substance acting as the luminescent center. In particular, the substance acting as 15 the luminescent center may be an element selected from the group consisting of europium, cerium and manganese. This provides a high luminous intensity.

The second compound semiconductor may contain $Mg_{1-x}Ca_xS$. Eu may be doped into $Mg_{1-x}Ca_xS$ as a substance acting as the 20 luminescent center, and the Eu composition ratio to Mg may be not larger than 0.1. Consequently, the deterioration of the crystallinity of $Mg_{1-x}Ca_xS$ due to doping of Eu is sufficiently suppressed, so that the degradation of luminous efficiency is prevented.

25 The Eu composition ratio to Mg is preferably not larger

than 0.01. Consequently, the deterioration of the crystallinity of $Mg_{1-x}Ca_xS$ due to doping of Eu is sufficiently suppressed, so that a high luminous intensity can be achieved.

A method of fabricating an inorganic electroluminescent device according to another aspect of the present invention comprises the steps of: forming an underlayer principally composed of a first compound semiconductor of Group IIa-VIb; and forming on the underlayer a light emitting layer principally composed of a second compound semiconductor of Group IIa-VIb having the same crystalline structure as that of the first compound semiconductor of Group IIa-VIb and doped with a substance acting as a luminescent center.

According to the method of this invention, on the underlayer principally composed of the first compound semiconductor of Group IIa-VIb, the light emitting layer principally composed of the second compound semiconductor of Group IIa-VIb having the same crystalline structure as that of the first compound semiconductor is formed, whereby the crystalline of the light emitting layer is improved, so that good optical characteristics are achieved. As a result, an inorganic electroluminescent device having good luminous characteristics can be fabricated.

The step of fabricating a underlayer preferably comprises a step of forming the underlayer at a first temperature, and the step of fabricating a light emitting layer

preferably comprises a step of forming the light emitting layer at a second temperature higher than the first temperature. In this case, the underlayer acts to prevent lack of an element in the light emitting layer during formation of the light emitting layer at an increased temperature. This allows the crystallinity of the light emitting layer to be improved to achieve further improved optical characteristics.

Preferably, the first temperature is not higher than 100°C, and the second temperature is higher than 100°C. In this case, forming the underlayer at the first temperature not higher than 100°C can sufficiently prevent lack of an element in the underlayer. Further, the underlayer acts to prevent lack of an element in the light emitting layer when the underlayer is formed at a temperature higher than 100°C. This allows the crystallinity of the light emitting layer to be sufficiently improved to achieve further improved optical characteristics.

In particular, the first temperature is preferably not lower than 20°C nor higher than 70°C. This allows the crystallinity of the light emitting layer to be sufficiently improved to achieve further improved optical characteristics.

The second temperature is preferably not lower than 150°C nor higher than 350°C. This allows the crystallinity of the light emitting layer to be further improved to achieve further improved optical characteristics. As a result, a high luminous

intensity can be achieved.

The first compound semiconductor may contain magnesium and sulfur, and the second compound semiconductor may contain magnesium and sulfur.

5 In this case, the light emitting layer containing magnesium and sulfur is formed on the underlayer containing magnesium and sulfur, whereby the underlayer acts to prevent lack of sulfur during formation of the light emitting layer at an increased temperature. This allows the crystallinity
10 of the light emitting layer to be improved to achieve good optical characteristics.

The second compound semiconductor may further contain calcium. In this case, the second compound semiconductor contains calcium in addition to magnesium and sulfur, thereby
15 achieving red light emission with high color purity.

The foregoing and other objects, features, aspects and advantages of the present invention will become more apparent from the following detailed description of the present invention when taken in conjunction with the accompanying
20 drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

Fig.1 is a schematic cross-sectional view showing the structure of an inorganic EL device according to one embodiment
25 of the present invention.

Fig.2 is a diagram showing the result of measurement of the X-ray diffraction pattern of MgS powder doped with Eu.

FIG.3 is a diagram showing the result of measurement of the substrate temperature dependency of X-ray diffraction 5 pattern of a $Mg_{0.9}Ca_{0.1}S$ film in the case where the $Mg_{0.9}Ca_{0.1}S$ film was formed on a substrate without a MgS film.

Fig.4 is a diagram showing the result of measurement of the substrate temperature dependency of X-ray diffraction pattern of a $Mg_{0.9}Ca_{0.1}S$ film in the case where the $Mg_{0.9}Ca_{0.1}S$ film 10 was formed on a substrate with a MgS film sandwiched therebetween.

Fig.5 is a diagram showing the result of measurement of the difference in the substrate temperature dependency of X-ray diffraction intensity of the $Mg_{0.9}Ca_{0.1}S$ film depending on 15 presence/absence of the MgS film.

Fig.6 is a diagram showing the result of measurement of the substrate temperature dependency of luminous intensity of a $Mg_{1-x}Ca_xS$ film depending on presence/absence of a MgS film.

Fig.7 is a diagram showing the result of measurement of 20 the underlayer film thickness dependency of an emission initiation voltage and luminous intensity of the inorganic EL device of Fig.1.

Fig.8 is a diagram showing the result of measurement of the Eu/Mg composition ratio dependency of luminous intensity 25 of the inorganic EL device of Fig.1.

Fig.9 is a diagram showing the result of measurement of the photoluminescent spectrum of $Mg_{1-x}Ca_xS$ films.

Fig.10 is a chromaticity diagram of the luminous color of a $Mg_{1-x}Ca_xS$ film in the case where the Ca composition ratio 5 x is varied from 0 to 1.0.

DESCRIPTION OF THE PREFERRED EMBODIMENTS

Description will now be made of an inorganic electroluminescent device (hereinafter abbreviated to an 10 inorganic EL device) according to one embodiment of the present invention.

Fig.1 is a schematic cross-sectional view showing the structure of an inorganic EL device according to one embodiment of the invention.

15 In Fig.1, a transparent electrode 2 composed of ITO (indium-tin oxide) with a thickness of 150 nm, a transparent insulating layer 3 composed of ZrSiN with a thickness of 100 to 300 nm, an underlayer 4 composed of MgS with a thickness of 100 to 300 nm, a light emitting layer 5 composed of $Mg_{1-x}Ca_xS$ with a thickness of 500 to 1000 nm, and an insulating layer 20 6 composed of ZrSiN with a thickness of 100 to 300 nm are formed on a glass substrate in this order. Electrodes 7 composed of Al with a thickness of not larger than 300 nm are formed on the insulating layer 6. While the description above has shown 25 preferred examples of materials and thicknesses of respective

layers, they are not exclusive in this invention.

The light emitting layer 5 is doped with Eu(europium) as a substance acting as a luminescent center. The Ca composition ratio x of $Mg_{1-x}Ca_xS$ in the light emitting layer 5 is preferably not smaller than 0 nor larger than 0.5. As will be described later, in order to obtain red light emission with high color purity at high efficiency, the Ca composition ratio x of $Mg_{1-x}Ca_xS$ in the light emitting layer 5 is more preferably $0.1 \leq x \leq 0.15$.

10 Description is next made of a method of fabricating the inorganic EL device of Fig.1. First, a transparent electrode 2 composed of ITO is formed on a glass substrate 1 by sputtering, and an insulating layer 3 composed of ZrSiN is formed on the transparent electrode 2 by sputtering. An underlayer 4 composed of MgS is formed on the insulating layer 3 by sputtering with the substrate temperature kept at room temperature without being heated. A light emitting layer 5 composed of $Mg_{1-x}Ca_xS$ doped with Eu is then formed on the underlayer 4 by sputtering with the substrate temperature set to higher than 100°C .
15 Further, an insulating layer 6 composed of ZrSiN is formed on the light emitting layer 5 by sputtering. Finally, electrodes 7 composed of Al are formed on the insulating layer 6 by vacuum vapor deposition.

During formation of the underlayer 4, the substrate
25 temperature is in the range of room temperature(approximately

20 °C) to approximately 100 °C, because of discharging of sputtering gas.

The "substrate temperature" herein represents temperature at which the substrate is maintained during film formation.

The insulating layer 3, the underlayer 4, the light emitting layer 5 and the insulating layer 6 are fabricated, for example, by radio frequency magnetron sputtering apparatus.

The Table 1 shows the representative sputtering conditions.

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(Table 1)

	insulating layer 3, 6	under layer 4	light emitting layer 5
target material	Si + Zr	MgS	MgS + CaS + EuS
sputtering gas	N ₂	Ar	Ar
gas pressure [Pa]	0.4	0.4	0.4
RF power [W/cm ²]	1.5	1.5	2.0
substrate temperature	200	room temperature	100~400

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In the inorganic EL device according to this embodiment, MgS of the underlayer 4 and Mg_{1-x}Ca_xS of the light emitting layer 5 have the same rock-salt structure. This allows the

crystallinity of the light emitting layer 5 on the underlayer 4 to be further improved, as will be described later, when the light emitting layer 5 is formed at an increased temperature.

In addition, the bandgap of the underlayer 4 is larger than the bandgap of the light emitting layer 5. Consequently, light emitted from the light emitting layer 5 is taken out transmitting through the underlayer 4, the insulating layer 3, the transparent electrode 2 and the glass substrate 1, without being absorbed by the underlayer 4. Accordingly, a high luminance can be achieved.

Here, $Mg_{1-x}Ca_xS$ films were formed on substrates at various substrate temperatures by sputtering under the same conditions shown in Table 1 except the substrate temperature, and then the substrate temperature dependency of X-ray diffraction pattern was measured. At the same time, $Mg_{1-x}Ca_xS$ films and MgS films were formed in this order on substrates at various substrate temperatures, and the substrate temperature dependency of X-ray diffraction pattern was measured.

Fig.2 is a diagram showing the result of measurement of the X-ray diffraction pattern of polycrystal MgS powder doped with Eu and annealed at 700°C. Further, Fig.3 is a diagram showing the result of measurement of the substrate temperature dependency of X-ray diffraction pattern of a $Mg_{0.9}Ca_{0.1}S$ film in the case where the $Mg_{0.9}Ca_{0.1}S$ film was formed without a MgS film on a substrate by sputtering, and (a), (b), (c), and (d)

show the cases at substrate temperatures of 100°C, 150°C, 200°C, and 300°C respectively. Fig. 4 is a diagram showing the result of measurement of the substrate temperature dependency of X-ray diffraction pattern of a $Mg_{0.9}Ca_{0.1}S$ film in the case where the 5 $Mg_{0.9}Ca_{0.1}S$ film was formed on a substrate with a MgS film sandwiched therebetween by sputtering, and (a), (b), (c), and (d) show the cases at substrate temperatures of 100°C, 150°C, 200°C, and 300°C respectively.

In Fig. 3, the thicknesses of the $Mg_{0.9}Ca_{0.1}S$ films of (a), 10 (b), (c), and (d) are 1161nm, 1116nm, 1287nm, and 918nm respectively. Further, in Fig. 4, the thicknesses of the $Mg_{0.9}Ca_{0.1}S$ films of (a), (b), (c), and (d) are 980nm, 1050nm, 950nm, and 970nm, respectively.

As shown in Fig. 2, as to the MgS powder annealed at 700°C, 15 there appear the diffraction peaks derived from the (200) plane, (111) plane and (220) plane while the diffraction peak derived from the (200) plane equivalent to the (100) plane remarkably appears.

As shown in Figs. 3 and 4, also as to the $Mg_{0.9}Ca_{0.1}S$ films, 20 there appears the remarkable diffraction peak derived from the (200) plane equivalent to the (100) plane, that is, the $Mg_{0.9}Ca_{0.1}S$ films have an orientation in a <100> direction. In the case of Fig. 3(d), however, there appears no diffraction peak.

As shown in Fig. 3 (a)-(d), in the cases where the $Mg_{0.9}Ca_{0.1}S$ 25 films were formed without the MgS films, the intensity of

diffraction peak derived from the (200) plane is decreased as the substrate temperature is increased. Thus, it is found that the crystallinity of a $Mg_{0.9}Ca_{0.1}S$ film is deteriorated with an increasing substrate temperature.

5 This is probably because increasing the substrate temperature in an effort to improve the crystallinity of the $Mg_{0.9}Ca_{0.1}S$ film causes lack of S in the $Mg_{0.9}Ca_{0.1}S$ film, thereby degrading the crystallinity of the film.

In contrast, as shown in Fig. 4 (a)-(d), in the cases where
10 the $Mg_{0.9}Ca_{0.1}S$ films were formed on the substrates with the MgS films sandwiched therebetween, the diffraction intensity becomes higher at each substrate temperature than each case where there is no underlayer as shown in Fig. 3 (a)-(d). Further,
15 the intensity of diffraction peak derived from the (200) plane is not decreased even when the substrate temperature is increased, and the intensity of diffraction peak becomes higher at a substrate temperature of 150°C than at a substrate temperature of 100°C, and becomes even higher at substrate temperatures of 200°C and 300°C. Therefore, it is found that
20 when the MgS film is formed as an underlayer, the crystallinity of the $Mg_{0.9}Ca_{0.1}S$ film is further improved than when there is no underlayer, and the crystallinity of the $Mg_{0.9}Ca_{0.1}S$ film is still further improved by setting the substrate temperature higher than 100°C during film formation.

25 This is probably because the MgS film acting as an

underlayer acts to suppress lack of S in the $Mg_{0.9}Ca_{0.1}S$ film, thereby forming the $Mg_{0.9}Ca_{0.1}S$ film so as to have high crystallinity at a high-temperature.

Fig.5 is a diagram showing the result of measurement of
5 the difference in the substrate temperature dependency of X-ray diffraction intensity of the $Mg_{0.9}Ca_{0.1}S$ film depending on presence/absence of the MgS film. Fig.5 shows the intensity of diffraction peak derived from the (200) plane shown in Figs.3 and 4.

10 As shown in Fig.5, without the MgS film, the intensity of X-ray diffraction of the $Mg_{0.9}Ca_{0.1}S$ film is decreased as the substrate temperature is decreased in the range of 100°C to 300°C. In contrast, with the MgS film, the intensity of X-ray diffraction of the $Mg_{0.9}Ca_{0.1}S$ film is increased with the
15 substrate temperature in the range of 100°C to 400°C.

The substrate temperature dependency of luminous intensity of a $Mg_{0.9}Ca_{0.1}S$ film was then measured depending on presence/absence of a MgS film. For the measurement, inorganic EL devices having the structure of Fig.1 and inorganic EL
20 devices having the same structure of Fig.1 except that the underlayer 4 is not formed were employed.

Fig.6 is a diagram showing the result of measurement of the substrate dependency of luminous intensity of a $Mg_{0.9}Ca_{0.1}S$ film depending on presence/absence of a MgS film.

25 As shown in Fig.6, with and without the MgS film, the

luminous intensity becomes higher with the substrate temperature higher than 100°C. In particular, the luminous intensity becomes high with the substrate temperature in the range of 150°C to 350°C, and with the MgS film, the luminous 5 intensity not less than a maximum value without the MgS film as an underlayer is obtained with the substrate temperature in the range of 160°C to 300°C, and furthermore, the luminous intensity becomes highest at a substrate temperature of 200°C. In addition, when the substrate temperature is higher than 100°C, 10 the luminous intensity becomes higher with the MgS film than when there is no MgS film.

It is found, therefore, that the optical characteristics of the $Mg_{0.9}Ca_{0.1}S$ film can be improved by forming the $Mg_{0.9}Ca_{0.1}S$ film on the MgS film, and setting the substrate temperature 15 higher than 100°C.

The results of Figs. 5 and 6 show that in fabricating the inorganic EL device of Fig. 1, it is preferable to set the substrate temperature higher than 100°C, more preferable in the range of 150°C to 350°C, and even more preferable in the 20 range of 160°C to 300°C.

The inorganic EL devices of Fig. 1 having various thicknesses of underlayers 4 composed of MgS were then fabricated, and the underlayer thickness dependency of emission initiation voltage and luminous intensity was 25 measured. Fig. 7 is a diagram showing the result of measurement

of the underlayer thickness dependency of emission initiation voltage and luminous intensity in the organic EL device of Fig.1.

As shown in Fig.7, the luminous intensity L is increased
5 as the thickness of the underlayer is increased, and it tends to be saturated with the thickness of the underlayer not smaller than 100 nm, and the luminous intensity L becomes saturated with the thickness of the underlayer not smaller than 500nm. In addition, the emission initiation voltage Vth becomes
10 sufficiently low with the thickness of the underlayer 200 nm, and the emission initiation voltage Vth becomes lowest with the thickness of the underlayer 100nm. The emission initiation voltage Vth is increased as the thickness of the underlayer is increased in the range of 100nm to 700nm.

15 Accordingly, in the inorganic EL device of Fig.1, in order to lower the emission initiation voltage Vth, it is preferable that the thickness of the underlayer 4 composed of MgS is not larger than 500 nm, more preferable not larger than 400 nm, even more preferable not larger than 200 nm. Furthermore, it
20 is preferable that the thickness of the underlayer 4 is not smaller than 100 nm in order to obtain a sufficiently high luminous intensity.

In order to obtain a sufficiently high luminous intensity while lowering the emission initiation voltage, it is
25 preferable to set the thickness of the underlayer 4 in the range

of 100 nm to 500 nm, more preferable in the range of 100 nm to 400 nm, and even more preferable in the range from 100 nm to 200 nm.

The Eu/Mg (concentration ratio) of the MgS powder or the
5 $Mg_{0.9}Ca_{0.1}S$ films in Figs. 2-7 above is 0.002.

Inorganic EL devices each having the structure of Fig. 1 with varied amounts of doping of Eu were then fabricated, and the Eu/Mg composition ratio (concentration ratio) dependency of luminous intensity in the light emitting layer was measured.

10 Fig. 8 is a diagram showing the result of measurement of the Eu/Mg composition ratio dependency of luminous intensity in the inorganic EL device of Fig. 1.

As shown in Fig. 8, the luminous intensity becomes high with the Eu/Mg composition ratio in the range of 0.001 to 0.02, 15 and becomes highest when the Eu/Mg composition ratio is 0.002.

Since deterioration of the crystallinity of the $Mg_{1-x}Ca_xS$ film occurs due to doping of Eu when the Eu/Mg composition ratio becomes not smaller than 0.1, it is preferable that Eu/Mg composition ratio is larger than 0 and not larger than 0.1. 20 In particular, from the result of Fig. 8, it is preferable that the Eu/Mg composition ratio is not smaller than 0.001 nor larger than 0.02, even more preferable not smaller than 0.0015 nor larger than 0.008.

The Ca composition ratio x in the light emitting layer 25 was varied at 0, 0.1, 0.2 and 1.0, and the photoluminescent (PL)

spectrum of the $Mg_{1-x}Ca_xS$ films were subsequently measured. the Eu/Mg composition ratio was set to 0.002. Fig.9 is a diagram showing the result of measurement of the photoluminescent(PL) spectrum of the $Mg_{1-x}Ca_xS$ films.

5 As shown in Fig.9, it is seen that the peak wavelength is largely shifted to the long-wavelength such as 590 nm, 630 nm, 650 nm, and 660 nm as the Ca composition ratio x of the $Mg_{1-x}Ca_xS$ film is increased at 0, 0.1, 0.2 and 1.0. Accordingly, it becomes possible to vary the light emitting wavelength by
10 adjusting the composition ratio x of Ca doped into the light emitting layer 5 composed of $Mg_{1-x}Ca_xS$.

Fig.10 is a chromaticity diagram of the luminescent color of the $Mg_{1-x}Ca_xS$ film when the Ca composition ratio x is varied from 0 to 1.0. The horizontal and vertical axes of Fig.10
15 indicate x and y coordinates respectively in the CIE chromaticity diagram.

As shown in Fig.10, the luminescent color changes from red-orange color to red color with an increase in the Ca composition ratio x of the $Mg_{1-x}Ca_xS$ film. Further, it is
20 possible to obtain the red color purity corresponding to a CRT(cathrode-ray tube) by doping Ca to satisfy the composition ratio x in the range of $0.1 \leq x \leq 0.15$.

While in the aforementioned embodiment Eu is doped into the light emitting layer 5 as a substance acting as a luminescent
25 center, a rare earth element such as Ce(cerium) or a transition

metal element such as Mn(manganese) may also be doped as an alternative substance acting as a luminescent center.

Furthermore, a rare earth element such as Eu or Ce or a transition metal element such as Mn(manganese) may also be 5 doped into the underlayer 4 as a substance acting as a luminescent center. In this case, the underlayer 4 as well as the light emitting layer 5 is allowed to emit light.

Although in the aforementioned embodiment, the description has been made of the case in which the respective 10 layers of the inorganic EL device are formed by sputtering, the invention is not limited to the method set out above, and it is also possible to form the respective layers of the inorganic EL device by other methods, such as vacuum vapor deposition or ion assisting vapor deposition.

15 Although the present invention has been described and illustrated in detail, it is clearly understood that the same is by way of illustration and example only and is not to be taken by way of limitation, the spirit and scope of the present invention being limited only by the terms of the appended 20 claims.